IN THE CLAIMS:

Please amend the claims as follows, adding new claims 40-46:

1.-10 (Cancelled)

- 11. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls, a substrate support, and a bottom of a processing chamber, comprising:
- a liner adapted to be removably disposed in the processing region and having a base for substantially covering the bottom of the processing chamber, wherein the liner further comprises:
- an outer cylindrical wall contacting an outer edge of the base for extending into the processing region along the sidewalls, the outer cylindrical wall having a first protrusion spaced above the base; and
- an inner cylindrical wall connected to an inner edge of the base for extending into the processing region along the substrate support, the inner cylindrical wall having a second protrusion located opposite the first protrusion; and
- a magnet located in the second protrusion on the inner cylindrical wall of the liner.
- 12. (Currently Amended) The apparatus of claim 11, wherein a <u>circular</u> passage is formed at least partially in the base, at least a portion of the <u>circular</u> passage is defined between the base and the bottom of the chamber, and the <u>circular</u> passage is adapted to fluidly isolate a heat transfer fluid flowing through the base.
- 13. (Currently Amended) The apparatus of claim 11, wherein the liner <u>has</u> further comprises:
 - a circular passage formed at least partially in the base; and
- a first boss and a second boss <u>interfacing with apertures formed in the bottom of</u>
 the processing chamber and projecting from the base, the first boss comprising a hole

in fluid communication with the <u>circular</u> passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the <u>circular</u> passage at an outlet of the passage.

- 14. (Currently Amended) The apparatus of clam 12, wherein the <u>circular</u> passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
- 15. (Currently Amended) The apparatus of claim 11, wherein the <u>inner</u> liner comprises a cylindrical wall <u>is sized to cover the substrate support with minimal clearance.</u>
- 16. (Currently Amended) The apparatus of claim 45 13, wherein the <u>circular</u> passage is formed at least partially in the bottom of the processing chamber evlindrical wall.
- 17. (Currently Amended) The apparatus of claim 45 13, wherein the <u>first boss and</u> the second boss aligns the base relative to the bottom of the processing chamber cylindrical wall comprises a lip extending into the process volume.
- 18. (Currently Amended) The apparatus of claim 15 11, wherein the cylindrical wall comprises a magnet comprises samarium disposed therein.
- 19. (Currently Amended) The apparatus of claim 45 13, wherein the first boss and the second boss cylindrical wall comprises:

a quick-connect coupling
a lip extending to the process volume; and
a magnet disposed therein.

20. (Currently Amended) The apparatus of claim 15 11, <u>further comprising:</u>
<u>a second liner coupled to the outer cylindrical wall along wherein the cylindrical wall is configured to line the sidewalls of the chamber and extending to a lid assembly.</u>

- 21. (Currently Amended) The apparatus of claim 45 20, wherein the second liner comprises an outwardly extending flange cylindrical wall is configured to line a substrate support disposed in the process volume of the chamber.
- 22. (Previously Presented) The apparatus of claim 11, wherein the liner further comprises:
- a passage formed at least partially in the base and adapted to fluidly isolate a heat transfer fluid flowing therethrough from the processing region, the passage being fluidly isolated from the processing region; and
 - a bottom coupled between the outer cylindrical wall and the inner cylindrical wall.
- 23. (Original) The apparatus of claim 11, wherein the liner is comprised of a material selected from the group of aluminum, ceramic and stainless steel.
- 24. (Original) The apparatus of claim 11, wherein the liner comprises: a textured interior surface adapted to be exposed to the interior volume.
- 25. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:

an annular base having a perimeter, for substantially covering the bottom of the processing chamber;

- a first cylindrical wall extending from the perimeter of the base:
- a substantially annular passage formed at least partially in the base; and
- a first boss and a second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the passage at an outlet of the passage, wherein the first boss and the second boss are configured to extend through the processing chamber.

- 26. (Original) The apparatus of claim 25, wherein the passage is adapted to isolate a heat transfer fluid flowing therethrough from the process volume.
- 27. (Cancelled)
- 28. (Original) The apparatus of clam 25, wherein the passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
- 29. (Original) The apparatus of claim 25, wherein the first cylindrical wall comprises a lip extending radially inwards in a spaced-apart relation to the base.
- 30. (Previously Presented) The apparatus of claim 25 further comprising a second cylindrical wall coupled to an inner portion of the base.
- 31. (Original) The apparatus of claim 25, wherein the base and first cylindrical wall are comprised of a material selected from the group of aluminum, ceramic and stainless steel.
- 32. (Original) The apparatus of claim 25, wherein the first cylindrical wall comprises a textured inner surface.
- 33. (Currently Amended) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:

an annular base for substantially covering the bottom of the chamber,

- a first cylindrical wall coupled to an outer portion of the base for extending into the processing region along the sidewalls of the chamber;
- a second cylindrical wall coupled to an inner portion of the base for extending into the processing region along a substrate support positioned therein;
- a ridge extending from the first cylindrical wall toward the second cylindrical wall in a spaced-apart relation to the base

a second cylindrical wall coupled to an inner portion of the base for extending into the processing region along a substrate support positioned therein; and

a substantially annular passage formed at least partially in the base, the passage being fluidly isolated from the processing region.

- 34. (Cancelled)
- 35. (Previously Presented) The apparatus of claim 33, wherein a passage is at least partially disposed in at least one of the first or second cylindrical walls.
- 36. (Currently Amended) A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:

a processing chamber having walls surrounding the processing region;

- a cylindrical liner section adapted to line at least a portion of the walls of the processing chamber;
- a center section coupled to one end of the cylindrical section, the cylindrical section and the center section being exposed to the processing region and comprising a single piece structure, for substantially covering an upper surface of the chamber; and
- a substantially annular passage at least partially formed in the center section, the passage being fluidly isolated from the processing region, wherein the substantially annular passage is coupled to a boss that extends through an aperture formed in the processing chamber.
- 37. (Currently Amended) A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:
- a <u>removable</u> center member for substantially covering an upper surface of the chamber, the center member having a first side adapted to be exposed to the processing region;
- a cylindrical wall extending from the first-side of the center member and adapted to line at least a portion of the walls of the processing chamber; and

a substantially annular passage at least partially formed in the center member, the passage adapted to isolate a heat transfer fluid flowing therethrough from the processing volume.

- 38. (Original) The apparatus of claim 37 further comprising a lid disposed proximate the center member and defining a plenum at least partially therewith.
- 39. (Original) The apparatus of claim 38, wherein the center member further comprises a plurality of nozzles disposed in the center member providing fluid access between the plenum and a side of the center member opposite the lid.
- 40. (New) The apparatus of claim 25, wherein the first boss and the second boss extend through apertures formed in the processing chamber to align the annular base.
- 41. (New) The apparatus of claim 33. wherein the bottom of the processing chamber comprises an aperture sized to receive a portion of the annular base.
- 42. (New) The apparatus of claim 41, wherein the aperture is sized to receive a boss coupled to the substantially annular passage.
- 43. (New) The apparatus of claim 41, wherein the first cylindrical wall and the annular base compress an o-ring positioned between the aperture and the annular base when a lid assembly is coupled to a top of the processing chamber.
- 44. (New) The apparatus of claim 33, wherein the bottom of the processing chamber further comprises:

an aperture to provide fluid to the substantially annular passage; and an o-ring to provide a seal between the annular base and the substantially annular passage.

- 45. (New) The apparatus of claim 36, wherein the boss and the aperture align the center section relative to the processing chamber.
- 46. (New) The apparatus of claim 45, wherein the aperture includes an o-ring that is compressed to form a seal between the processing chamber and the center section.